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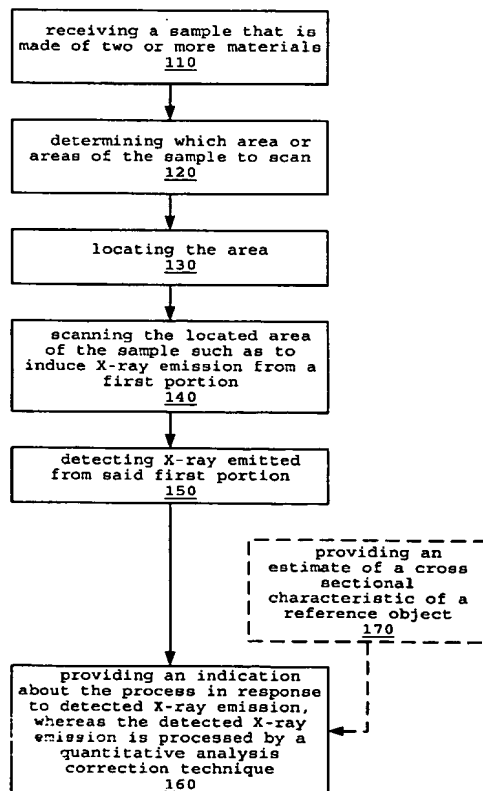
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- (71) Applicant (for all designated States except US, ZW): APPLIED MATERIALS ISRAEL, LTD. [IL/IL]; 8 Oppenheimer Street, 76236 Rehovot (IL).
- (71) Applicant (for ZW only): APPLIED MATERIALS, INC. [US/US]; P.O. Box 450A, Santa Clara, CA 95052 (US).
- (72) Inventor; and
- (75) Inventor/Applicant (for US only): SHEMESH, Dror [IL/IL]; Ben Zvi 17, 49375 Petah Tikva (IL).
- (74) Agent: FAHMI, Tarek, N.; Blakely, Sokoloff, Taylor & Zafman LLP, 12400 Wilshire Boulevard, 7th Floor, Los Angeles, CA 90025 (US).
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(54) Title: METHODS AND SYSTEMS FOR PROCESS MONITORING



(57) Abstract: Systems and methods for process monitoring based upon X-ray emission induced by a beam of charged particles such as electrons or ions include a system and method for process monitoring that analyze a cavity before being filled and then analyze emitted X-rays from the cavity after the cavity has been filled with a conductive material. Also included are system and methods for process monitoring that apply a quantitative analysis correction technique on detected X-ray emissions.

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